

Amended claim 1 includes the following features:

- a substrate, the substrate comprising a surface;
- a first device and a second device formed within the substrate;
- an isolation region formed within the substrate between the first device and the second device, the isolation region comprising:
  - a deep region which extends into the substrate, the deep region comprising a deep region cross-sectional area;
  - a shallow region which extends to the surface of the substrate, the shallow region comprising:
    - a protective outer wall adjacent to the substrate;
    - an inner sealing wall located within the protective outer wall; and
    - the shallow region having a shallow region cross-sectional area;
- wherein
- the deep region cross-sectional area is greater than the shallow region cross-sectional area.

(Emphasis Added)

Support for the amendments can be found in the specification on page 7, lines 4-17. Additionally, these features are shown in Figure 3.

Murakami does not teach or discuss a protective outer wall adjacent to the substrate and an inner sealing wall located within the protective outer wall.

Murakami cannot be combined with Ho to yield the invention. The  $\text{Si}_3\text{N}_4$  liner of Ho et al., US patent No. 5,747,866 is only applied to a shallow trench. The protective outer wall adjacent to the substrate and inner sealing wall located within the protective outer wall of the invention are included within a shallow region of an isolation region that further includes a deep region. The invention is not obvious through the combination of Murakami and Ho because there are no suggestions or teachings by either reference to form an inner sealing wall in a shallow region exclusively. Additionally, neither of the references suggest a method of forming the isolation structure of the invention.

Claim 1 is patentable over the cited references.

Claim 3 has been deleted.

Amended claim 5 includes the same new features as amended claim 1. Claim 5 is patentable over the cited references.

The Examiner rejected claim 2 under 35USC103(a) as being unpatentable over Murakami as applied to claims 1.

Claim 2 is dependent on claim 1. Therefore, claim 2 is patentable.

Claims 4 and 6 were rejected under 35USC103(a) as being unpatentable over Murakami as applied to claim 1-3 above, and further in view of Ho et al., US patent No. 5,747,866.

Claim 4 is dependent on claim 1. Therefore, claim 4 is patentable.

Claim 6 is dependent on claim 5. Therefore, claim 6 is patentable.

None of the references cited by the Examiner teach or suggest the inventive concepts of the present invention.

No new information has been added with these amendments.

The Applicants respectfully request reconsideration of the claims in view of the remarks made herein. A notice of allowance is earnestly solicited.

Respectfully submitted,  
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